

IN THE SPECIFICATION:

Please amend paragraphs 0099, 0110, and 0130 of the specification as follows.

[0099] Fig. 8 illustrates the main part of a micro-asperity pattern forming apparatus 1G according to a seventh embodiment for forming an asperity pattern on a resin thin film.

The seventh embodiment of Fig. 8 is different from the third embodiment of Fig. 4 in that the pressurizing mechanism 2A which holds the embossment roll 3A rotatably by pressurizing mechanisms 2a and 2b is configured so as to be movable in the vertical direction while applying pressure to the resin thin film 4, and that a moving mechanism 8A is placed on an embossment-roll-rotation-axis-direction moving mechanism 8B so as to be movable in the embossment roll rotation axis direction.

[0110] Next, the alignment marks will be described with reference to Figs. 11A-11D. In the case of a color liquid crystal display device, as shown in Figs. 11A and 11B, alignment marks 5a and 5b or 22 are provided to register a color filter layer (not shown) with the liquid crystal driving elements 31 that are formed on the substrate 5. Likewise, in Fig. 11C alignment marks 5c and 5d or 22 can also be seen.

[0130] In this embodiment, the two alignment mark observation optical devices 29Aa and 29Ab are used. Alternatively, one or four alignment mark observation optical devices may be used 29Aa, 29Ab, 29Ba, and 29Bb. In this case, position deviations of the alignment marks are determined by driving the embossment-roll-rotation-axis-direction moving mechanism 8B or the moving mechanism 8A and the deviations from the reference positions are made within the prescribed reference value by driving the substrate rotation direction adjustment mechanism 16B.